

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		10/782,821	FUTATSUYA ET AL.	
Examiner		Art Unit		Page 1 of 3
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*	B	US-5,278,421	01-1994	Yoda et al.	250/492.22
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	M	US-			

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	V	Bruno La Fontaine et al.; "Analysis of Flare and its Impact on Low-k1 KrF and ArF Lithography", 2002, Proceedings of the SPIE, Volume 4691, pages 44 - 56
	W	Andreas Erdmann et al.; "Enhancements in Rigorous Simulation of Light Diffraction from Phase Shift Masks", 2002, Proceedings of SPIE, Volume 4691, pages 1156 - 1167
	X	Chris A. Mack; "Measuring and Modeling Flare in Optical Lithography", June 2003, Optical Microlithography XVI, Proceedings of the SPIE, Volume 5040, pp. 151-161

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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